

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: N. William Parker et al. Docket No.: 58884-0305279
(MBS-0005US)

Serial No.: Continuation of 10/243,585 Group Art Unit:
Filing Date: July 28, 2003 Examiner:

For: **ELECTRON OPTICS FOR MULTI-BEAM ELECTRON BEAM LITHOGRAPHY TOOL**

PRELIMINARY AMENDMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Please enter this amendment prior to examination of the enclosed continuation application:

AMENDMENT

IN THE CLAIMS

Cancel claims 1-6 as filed in the parent application.

Add the following new claims:

- 1 7. (New) An electron optical column comprising:
 - 2 means for generating an electron beam;
 - 3 a focus lens; and
 - 4 an electrostatic scanning deflector situated above said focus lens, said scanning deflector
 - 5 comprising a first deflector and a second deflector configured to provide telecentric scanning of
 - 6 said electron beam on a specimen substrate positioned below said focus lens.

- 1 8. (New) An electron optical column as in claim 1, wherein said first deflector and said
- 2 second deflector generate electric fields of opposite polarities.

- 1 9. (New) An electron optical column as in claim 1, wherein said first deflector and said